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Integrated circuits were developed following Moore's law, which predicted that the degree of microprocessor integration would double every 18 months in dynamic random-access memory (DRAM). However, as the size of circuit elements approaches its physical limit, the optical method used in manufacturing 16 nm-node chips is also approaching a limit. Although the scaling of microelectronic circuit elements still follows Moore's law, the unit density of power consumption will become unacceptable. Therefore, on the one hand, while the microelectronic technology is being developed continuously, on the other, the feasibility of overcoming Moore's law is also being considered—that is, the More than Moore strategy.

Physically, when the scale of the circuit elements decreases to 10 nm or even less, the quantum effect appears and plays a more and more important role. The electron transport becomes non-classical and non-linear. Even electron motion is like waveguide motion. This book introduces some interesting theories and experiments related to quantum transport. It consists of two parts: (i) Non-classical, Non-linear Transport, and (ii) Quantum Waveguide Theory in Mesoscopic Systems. It provides solid foundations for semiconductor micro- and nanoelectronics for the after-Moore age, develops the transfer matrix method and uses it to study the Rashba electron transport in the Aharonov–Bohm circular ring and square ring, and discusses theories in view of their applications in next-generation semiconductor electronics and industry.



Jian-Bai Xia is a professor at the Institute of Semiconductors, Chinese Academy of Sciences, Beijing. He has many firsts to his credit. Prof. Xia was the first to propose the plane wave expansion method, the tensor model of quantum spheres, the effective-mass theory of (11N)-oriented superlattices, and hole tunneling theory. He developed a systematic method in the framework of the effective-mass theory to study the electronic structures of quantum dots and wires in a magnetic or electric field, especially spin-related properties, besides predicting a series of new phenomena relating to quantum dots, quantum wires, and nanofilms. A recipient of many awards and honors, Prof. Xia has published more than 105 articles, authored or coauthored 2 monographs, and served in important capacities in several universities.



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